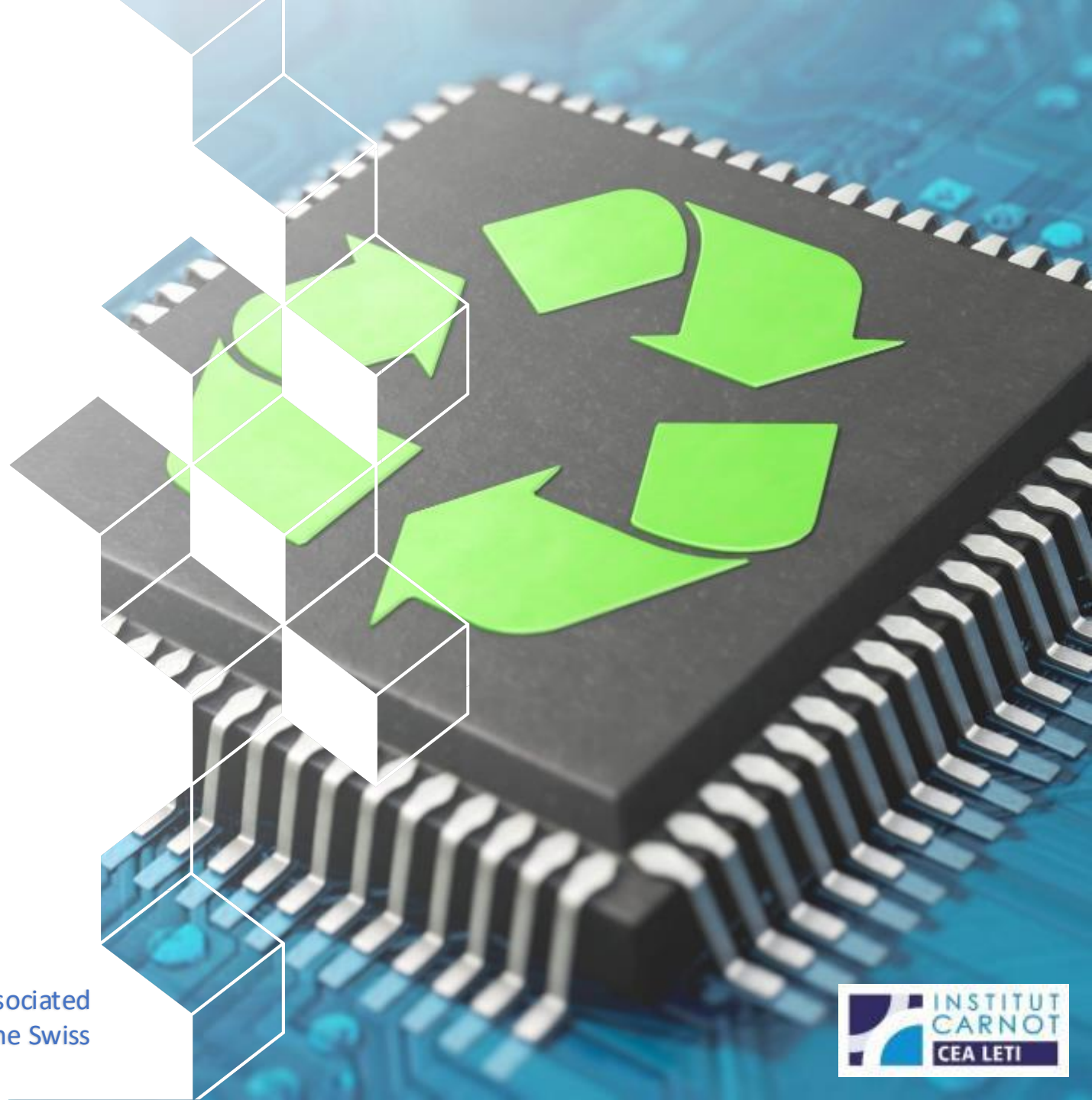




ENABLING RESILIENCE AND CIRCULARITY IN SEMICONDUCTOR MANUFACTURING

Laurent PAIN

Sustainable Electronics Program Director, CEA-Leti

Contact : laurent.pain@cea.fr

GENESIS and FAMES are EU programs supported by CHIPS JU and its associated members states. In addition, GENESIS Swiss partners are supported by the Swiss state secretariat (SERI)

Summary

1. Introduction
2. 1st need : impact identification
3. A more sustainable ICT manufacturing
The **SUBFAB Labs** initiative
4. Development around integration & systems
5. Conclusions

ICT INDUSTRY PARADIGM



Health



Automotive



Industry



Smart cities



Energy management



Agriculture

ICT INDUSTRY PARADIGM



Health



Automotive



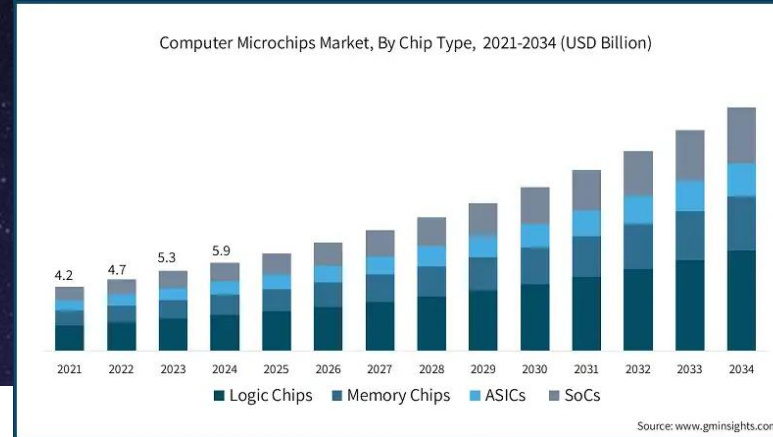
Industry



Smart cities

HOW TO MATCH IC MARKET
WITH SUSTAINABILITY CONCERNS

ICT FORECAST...



More chips, more water

Rising capex is expanding semiconductor manufacturing, driving up water demand



...more water...

...More chips...

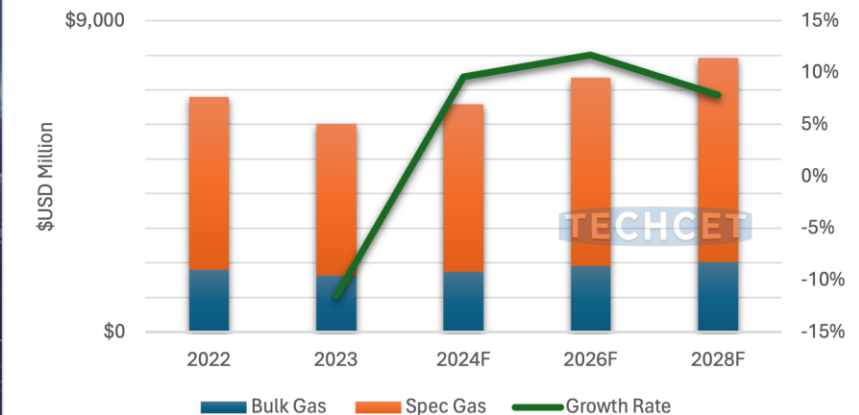
63 Mton of e-waste in 2030



0.4-2.5 from data centres Due to generative AI

...more wastes...

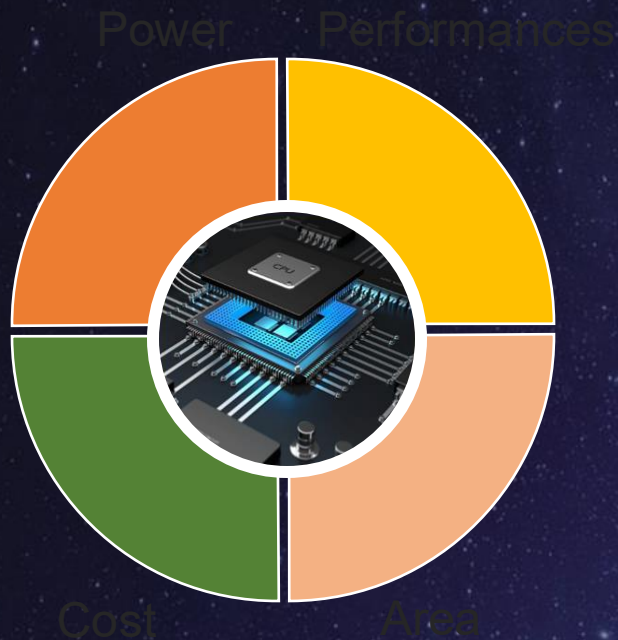
Electronic Gas Market Forecast



...more PFC!

Urgent need to pave the route toward a sustainable electronic

<https://mobilitynotes.com/european-critical-raw-materials-act/>



EU Critical Raw Materials Act
Critical Raw Materials Marked with Color
Strategic Raw Material

Transition metals	Alkali metals	Nonmetal
Co	Li	C
Cu	Na	N
Fe	K	O
Ni	Rb	S
Pd	Cs	Se
Sn	Fr	Te
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Summary

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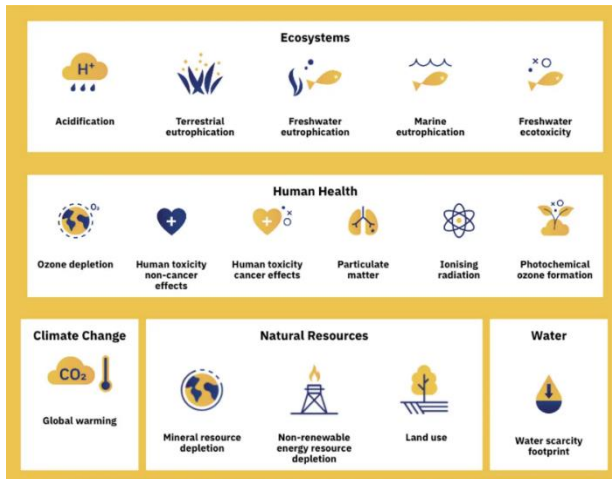
Understand environmental impact

Dynamic LCA solutions

1

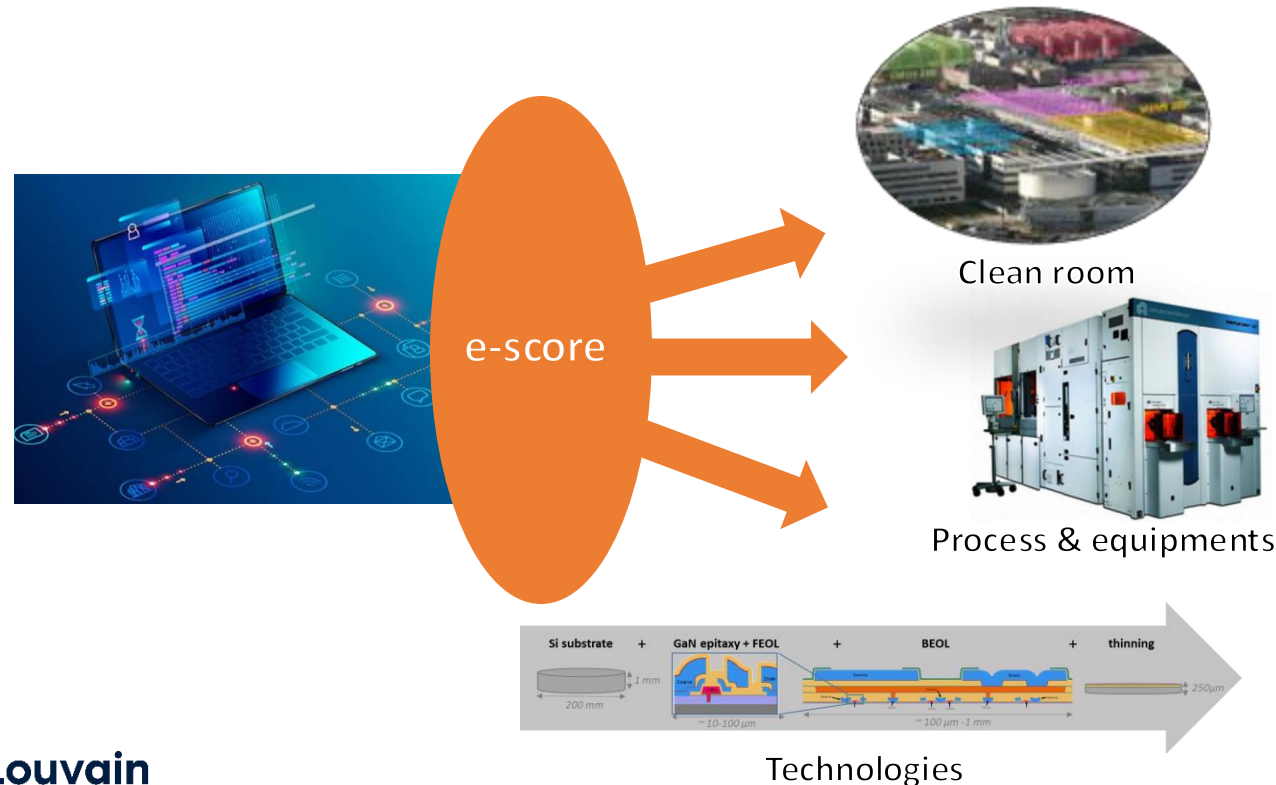
LCA methods
comparative, absolute

16 environmental footprint impacts



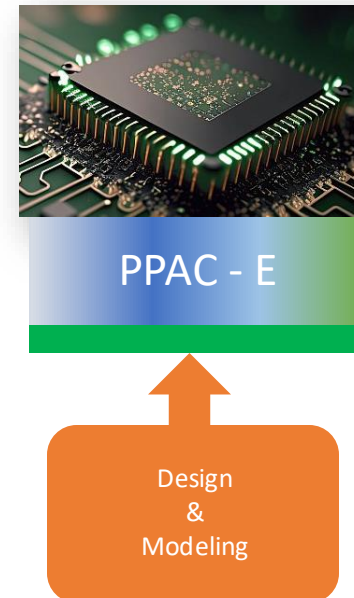
2

Dynamic e-score LCA SW platform



3

Eco design solution



Joint work with : **imec** **UCLouvain**

Summary

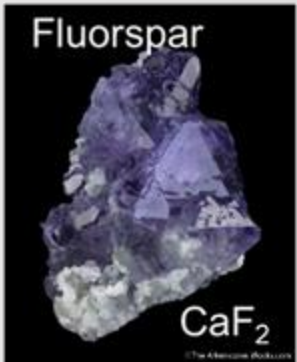
1. Introduction
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The challenge for a more sustainable IC industry

Etch gas process example



Revisit raw materials

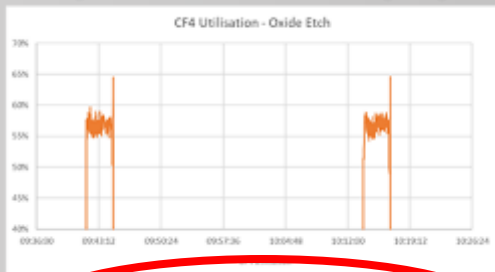


Optimise material process

Literature carbon intensities
CH₂F₂ manufacturing
~10 kg CO₂eq/kg CH₂F₂

Fab Process

Consider global impact
Use phase and by-product



dielectric etch chamber
45% of CF₄ not used

Emissions:

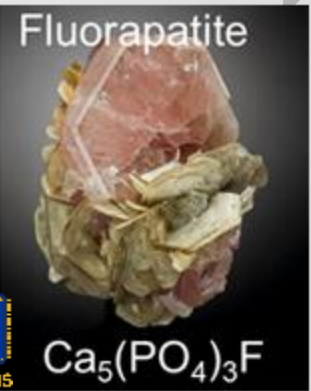
- Production
- Use
- Abatement

HF sources

Fluorinated Materials

Applications & Abatement

Final waste



Electronic grade
purification impact

increase carbon footprint
10-1000x

Courtesy from **ARKEMA**

Contact etch chamber
Up to 85% of CF₄ not used



Results from CEA-Leti pilot line with **EDWARDS**

Deposition

- Soil
- Surface Water
- Ocean



1ST CEA-LETI PARTNERSHIP ENGAGEMENTS



JU Chips GENESIS

Develop & qualify solution to improve ICT manufacturing sustainability
(TRL 3 → 6)

JU Chips FAMES

CEA-Leti FDSOI 10/7nm Pilot line

WP Sustainability

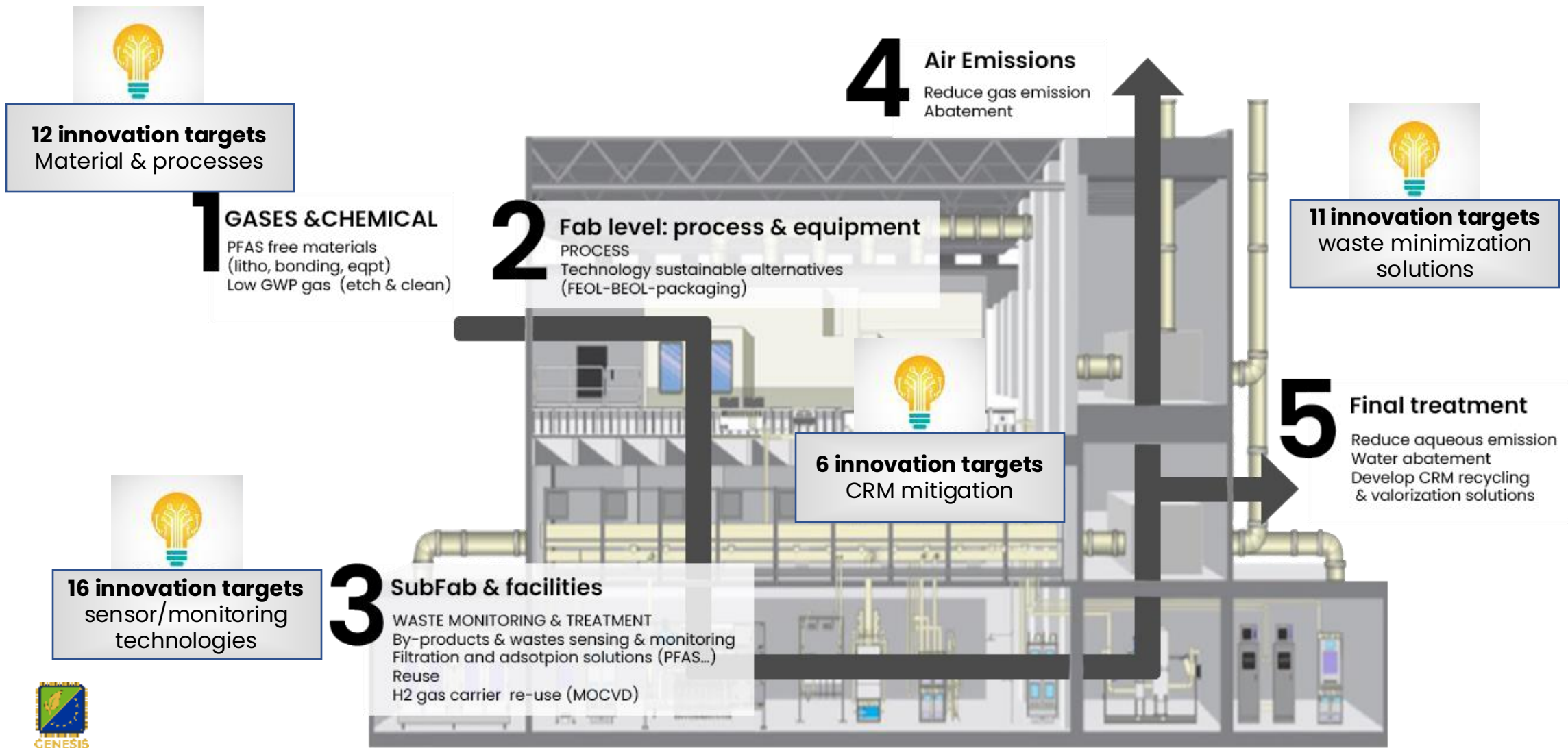
Methodology & impact scoring
Pilot line impact reduction
Eco-design

Improved
IC
manufacturing



GENESIS objectives

→ Improve the entire manufacturing sustainability chain value



1ST CEA-LETI PARTNERSHIP ENGAGEMENTS

JU Chips GENESIS

Develop & qualify solution to improve ICT manufacturing sustainability
(TRL 3 → 6)

SUBFAB LABS

(Program frame work : Affiliate & institutional)
Scale up solution to boost technologies & sustainability improvement in SUBFAB environment
(TRL>5)

JU Chips FAMES

CEA-Leti FDSOI 10/7nm Pilot line

WP Sustainability

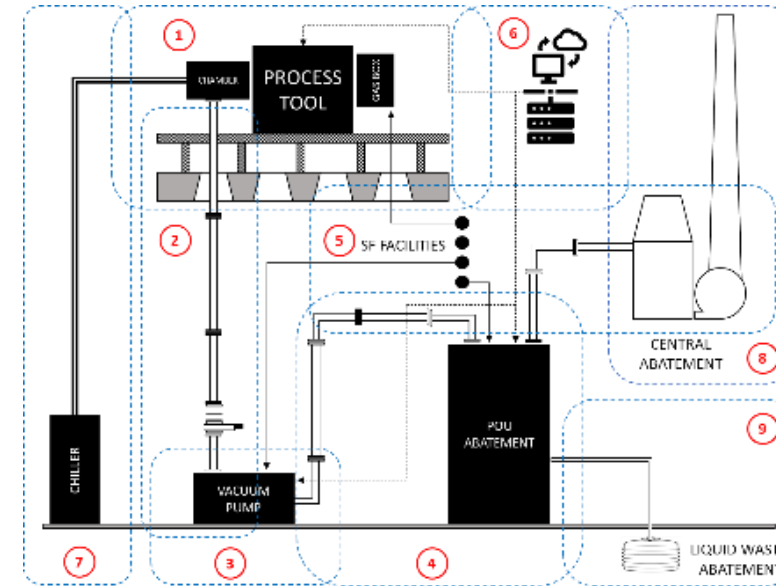
Methodology & impact scoring
Pilot line impact reduction
Eco-design

Improved
IC
manufacturing

SUBFAB LABS AMBITION

A dedicated environment to RETHINK SUBFAB

HVM-like
working
operations
24/24



Program
Co-driven with



→ Objectives :

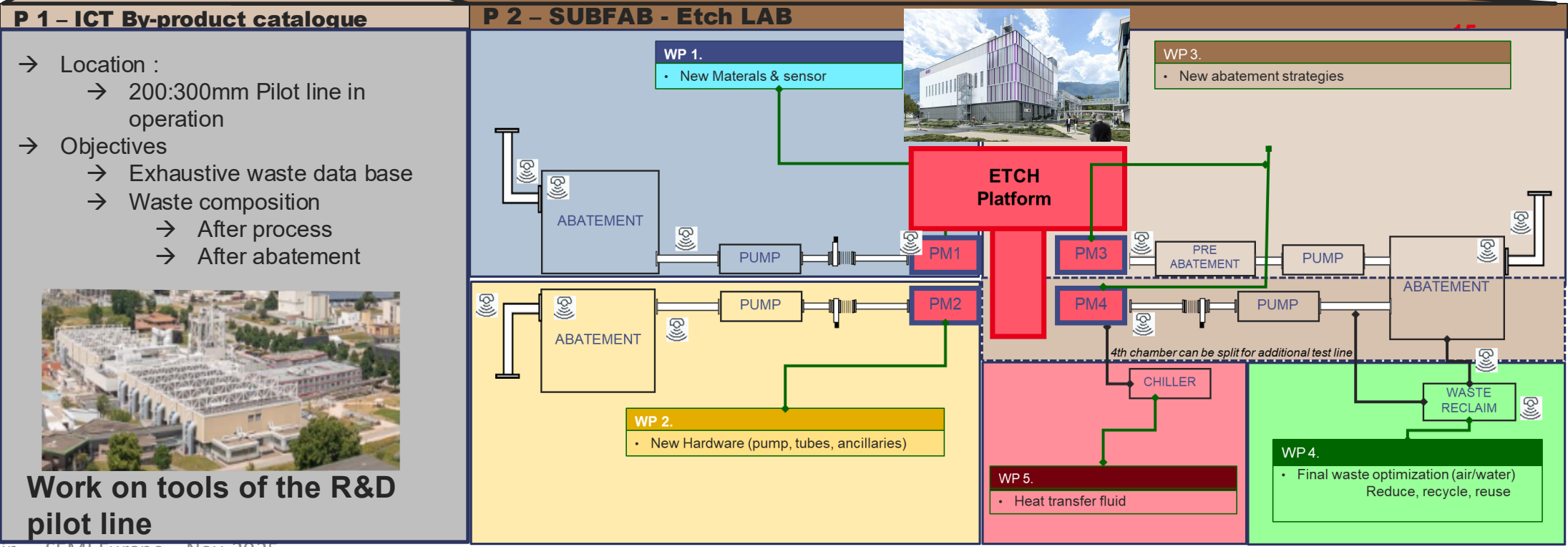
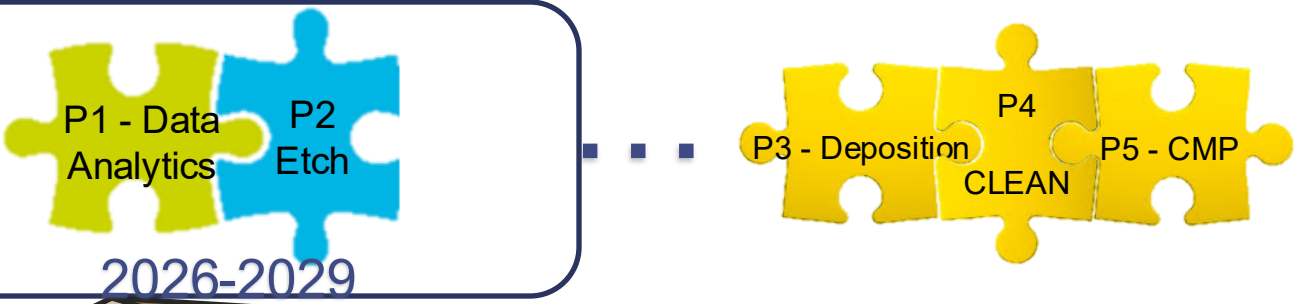
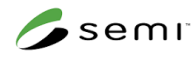
- Improve material and Hardware use, waste management policy (sensing, circularity, waste treatment...)
 - Qualify new solutions in « certified prod- like condition mode »
 - Fab modelling data to evaluate economical and sustainability impacts
- ### → An environment open tailored for partners to :
- Evaluate new Hardware (pumps, abatement...) in intensive mode
 - Qualify new materials (Low GWP gas, PFAS free resist..)
 - Mature new breakthrough solutions on process, sensing strategy, waste management incl. minimization, recycling/re-use, data handling

SUBFAB LABS environment

Rethink a more sustainable SUBFAB



Affiliate program
Co-driven with



Work on tools of the R&D pilot line

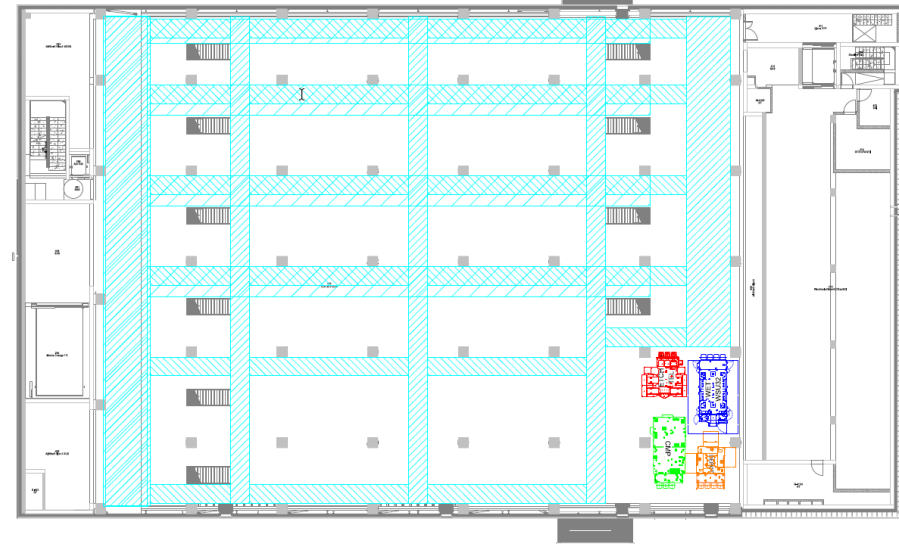


SUBFAB LABS location

4103– New LETI fab



Building: 4103 ✓
Environment: 2 level of basement (clean & dirty) ✓
Facility status : Facilities already pre-aquiped ✓
6 aqueous segregation lines available



4103 new CEA-Leti facilities
State of the art facilities

Experimental floorplant reserved compatible with 4 equipments config



PHASE 1 – By-product data analysis



- Test line infrastructure
 - 200/300 CEA-Leti pilot line
 - Data analytic performed with sensor partners
- Test protocol (per process family)
 - DOE : define process boundaries and experimental set-up
 - Process tests
 - Specific DOE
 - Hook-up (if needed) of post process line for sensor installation
 - Measurement campaign
 - Result analysis and report
 - Removal of sensor for next process monitoring

CEA-Leti pilot line etch & deposition potential portfolio

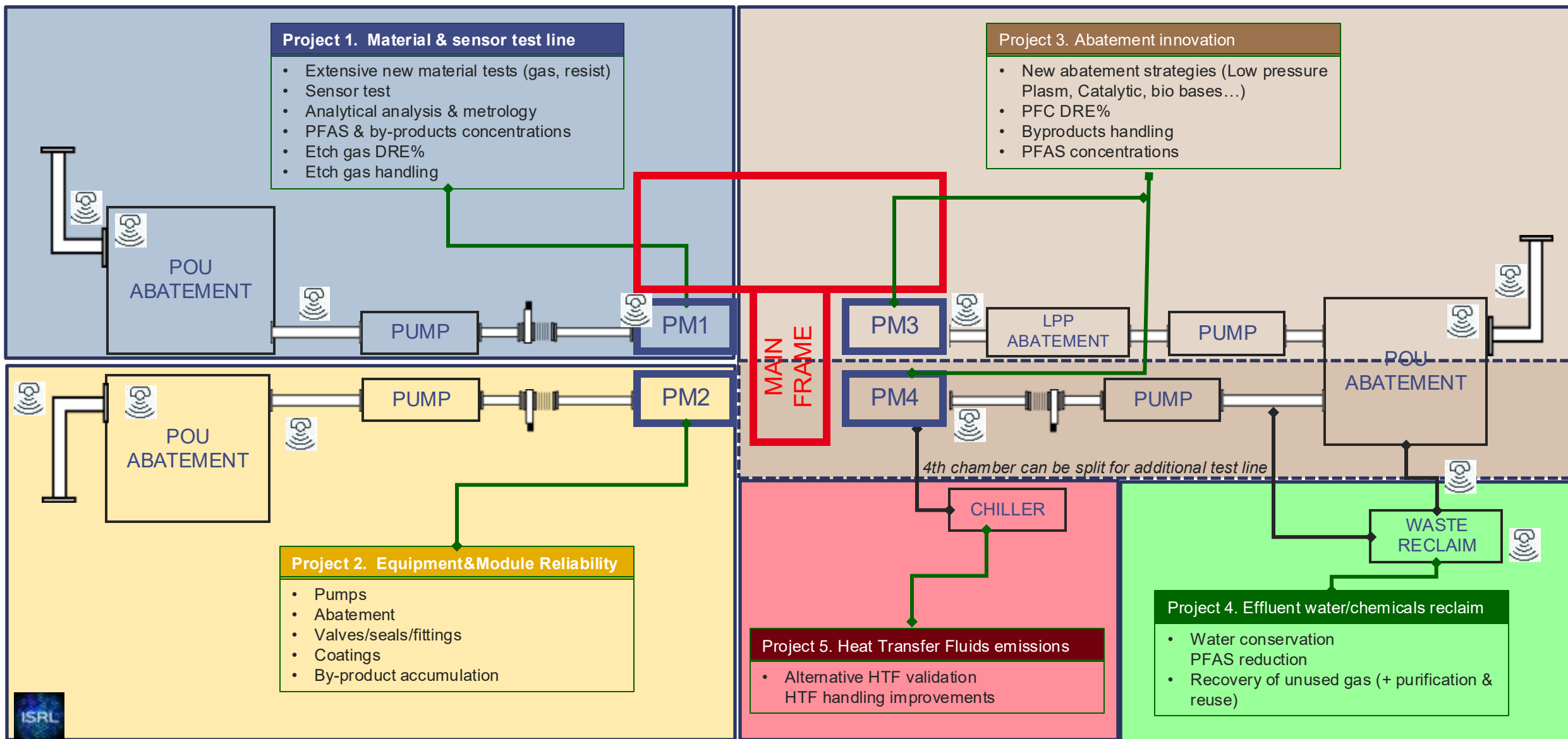
By-product data analysis – Etch



By-product data analysis – deposition



PHASE 2 – SUBFAB LAB Etch post process



SubFab solution outcomes



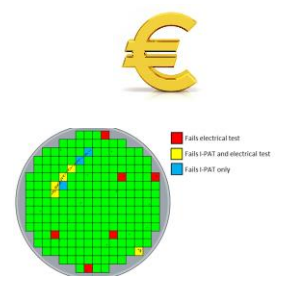
-  **Cost reduction** : energy efficiency, raw materials, waste reduction, ...
-  **Unique opportunity** to access a dedicated HVM line platform **without impacting your production environment**
-  **Competitive advantage**: product innovation + "green" differentiation
-  **Access to green financing and public subsidies**
-  **Improved ESG score**
-  **Less dependence on critical resources** (rare gases, materials, water, energy, ...)



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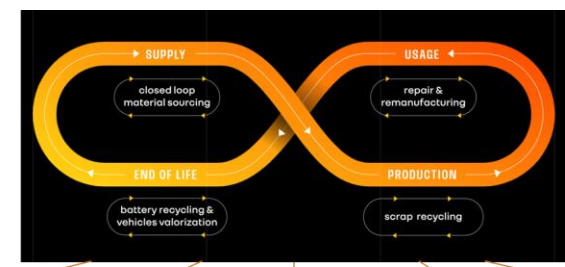
6R POLICY FOR CIRCULAR & LONG LASTING



The cohabitation challenge between Sustainability & ICT

Renault group ambition

First company with 360° operation across the entire automotive value chain, from the supply of parts and raw materials to the vehicles' end-of-life (ELV).



- INDRA (Recycling ELV)
- GAIA (Recycling Materials)
- THE REMAKERS (Remanufacturing)
- BCM (Metal waste Mgt)
- Battery Recycling

EXTEND LIFETIME : POWER CONVERTER CASE

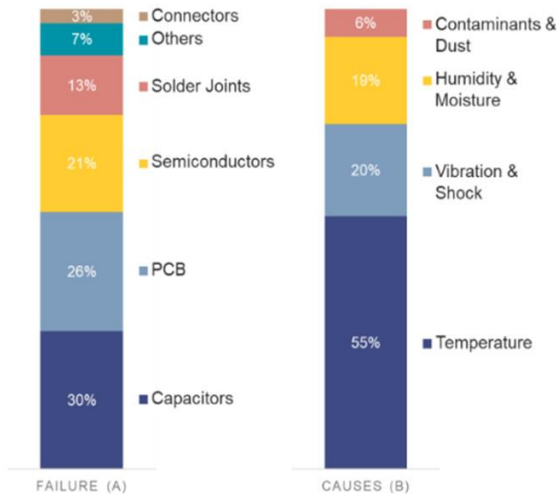


Fig. 1. Failures impacts (a) and associated causes (b) in power electronic systems

Y. Fassi et al. "Towards Physics-Informed Machine Learning-Based Predictive Maintenance for Power Converters – A Review," *IEEE Transactions on Power Electronics*, pp. 1–33, 2023

1 - Model based

- Grounded in physics,
- Allow to simulate multiple failure modes
- But complex to implement, time consuming, no real time

2 - Data driven

- Flexible
- But often ignore physics
- Lack of experiment data of failure

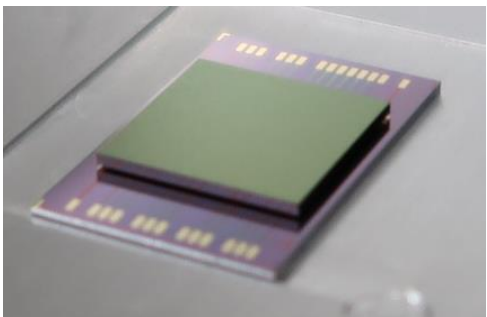
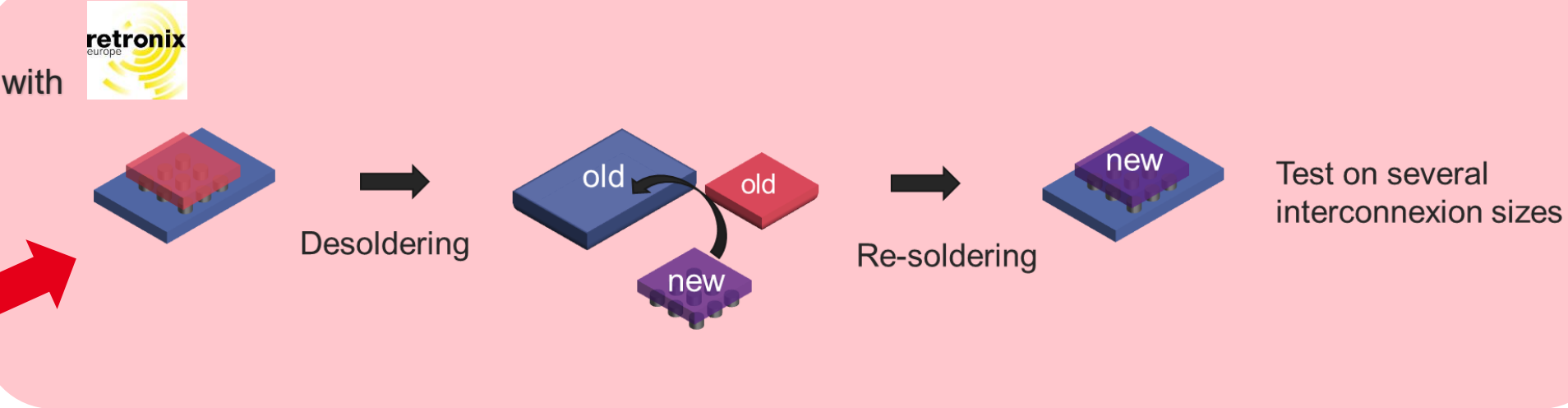
3 - PINN

(Physics Informed Neural Network)

- Combining AI & physics
- Trade-off: accuracy vs. physical consistency

REPAIR

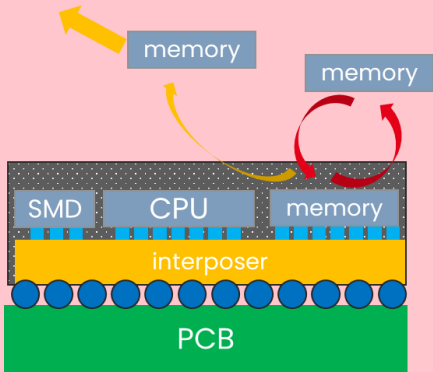
At component level



Source: CEA



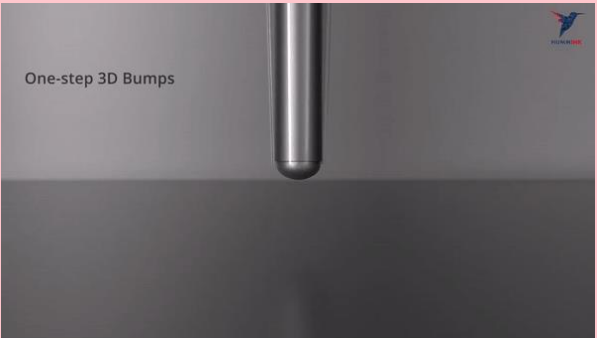
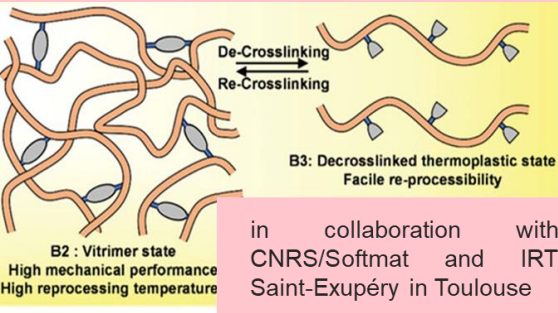
At package level



New polymer needs
Vitrimers



Additive
manufacturing



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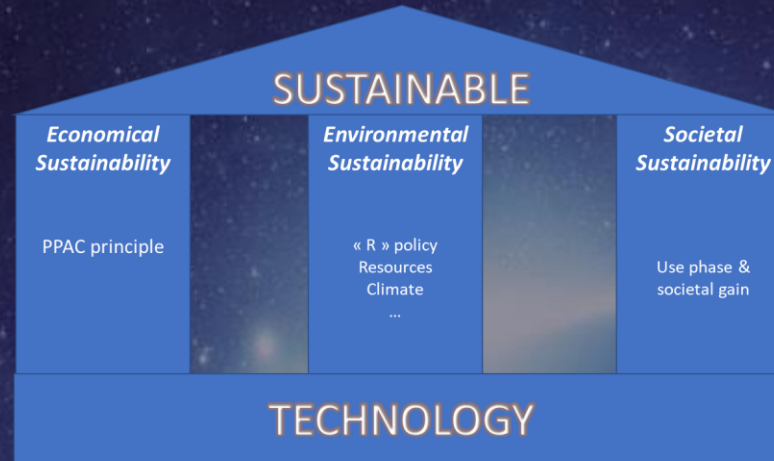
THE ROAD TOWARD A MORE SUSTAINABLE INDUSTRY

+1,5°C Global warning before 2030 becomes nowadays an evidence
« Science without conscience is only ruin of the soul »

... AND A MOTIVATION TO SPEED EFFORT

PARTNERSHIP

SUBFABLABS synergies



BREAKTHROUGH
PROGRESS

Synergies

Complementarities
(Top/down data...)

SUBFAB LABS

Target : Worldwide consortium

- Close link with SEMI for roadmap
- Dedicated experimental environment
- Evaluate and qualify solutions (material, HW) in HVM mode
- Operational platform 24/24 5/7
- Calculate impact benefits on HVM condition (environmental & economical) – Upscale result through modelling to real fabs

SEMI & SCC

- Worldwide consortium – 100 partners approx
- Draw roadmap to reach carbon neutrality @2050
- Identify potential technologies for the members
- Create standards and reporting rules for IC industry

IMEC & SSTs

- Worldwide consortium
- SW environment to calculate technology impact (climate and coming water, resource)
- Data base issue from top/down industry & estimation from R&D (with industry projection)

Sustainable Electronic

Green
Manufacturing



PPAC - E

Eco-design

ACKNOWLEDGMENTS



- **GENESIS and FAMES are EU programs supported by CHIPS JU and its associated member states. In addition, GENESIS Swiss partners are supported by the Swiss state secretariat (SERI)**
- **Special thanks to ISRL & SEMI**
- **Thanks to ARKEMA, and Edwards for their support**